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## **Supporting Information**

## Reversible Transformation of Sub-nanometer Ga-based Clusters to Isolated <sup>[4]</sup>Ga<sub>(4Si)</sub> Sites Creates Active Centers for Propane Dehydrogenation

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## FIGURES

Figure S1. XRD pattern of Ga1 <sub>(650)</sub> .	3
Figure S2. XANES comparison of Ga1(500-air), Ga1(650) and the reference material Ga(acac)3	3
Figure S3. Ga K-edge Fourier transformed EXAFS functions (non-phase corrected) of Ga1 <sub>(500-air)</sub> and	
Ga1 <sub>(650)</sub> collected at 50 °C	4
Figure S4. EXAFS fittings of Ga1 <sub>(500-air)</sub> at Ga K-edge: magnitude (top) and imaginary (bottom) parts of	:
the FT in R space	1
Figure S5. EXAFS fittings of Ga1 <sub>(650)</sub> at Ga K-edge: magnitude (top) and imaginary (bottom) parts of	
the FT in R space	5
<b>Figure S6.</b> Wavelet transform (WT) analysis of EXAFS data for Ga1 <sub>(500-air)</sub> in the R range: (a) 0.5-4 Å and (b) 2-4 Å.	5
<b>Figure S7.</b> Wavelet transform (WT) analysis of EXAFS data for Ga1 <sub>(650)</sub> in the R range: (a) 0.5-4 Å and (b) 2-4 Å.	5
Figure S8. (a) ADF-STEM image and (b) EXD mapping of Ga1 <sub>(650,air</sub> ).	5
<b>Figure S9.</b> (a) Atomic and weight percentage of Ga content, (b) EDX spectrum and (c) ADF-STEM	
image and EDX mappings of a selected area of Ga1 <sub>(650-air)</sub>	6
<b>Figure S10.</b> FTIR spectra of SOMC-prepared Ga@SiO <sub>2</sub> after evacuation at 650 °C and CO adsorption at a pressure of 20 Torr at room temperature.	7
<b>Figure S11.</b> FTIR spectra of SiO <sub>2</sub> in the hydroxyl region outgassed at 300, 400 or 550 °C.	7
Figure S12. FTIR comparison of the hydroxyl region of SiO <sub>2</sub> and Ga1 <sub>(500-air)</sub> after evacuation at 300 °C.	
8	3
Figure S13. Comparison of the <sup>71</sup> Ga MAS NMR spectra (obtained at 20.0 T with a spinning rate of	
64 kHz) of Ga1 <sub>(500-air)</sub> and Ga1 <sub>(650-air)</sub> alongside the reference β-Ga <sub>2</sub> O <sub>3</sub>	3
Figure S14. Propane conversion and product formation rate (mg h <sup>-1</sup> $g_{cat}^{-1}$ ) of C <sub>3</sub> H <sub>6</sub> (blue), C <sub>2</sub> H <sub>4</sub> (green	)
and CH <sub>4</sub> (yellow) on Ga1 <sub>(650)</sub> over 20 h TOS	Э
Figure S15. Normalized propene formation rate ( $g_{C3H6}$ h <sup>-1</sup> $g_{Ga}^{-1}$ m <sup>-2</sup> ) on Ga1 <sub>(650)</sub> over 25 h (5 × 5 h)	
TOS including four regeneration cycles (synthetic air, 550 °C, 1 h) performed after every 5 h	Э



Figure S1. XRD pattern of Ga1<sub>(650)</sub>.



Figure S2. XANES comparison of  $Ga1_{(500-air)}$ ,  $Ga1_{(650)}$  and the reference material  $Ga(acac)_3$ .



**Figure S3.** Ga K-edge Fourier transformed EXAFS functions (non-phase corrected) of  $Ga1_{(500-air)}$  and  $Ga1_{(650)}$  collected at 50 °C.



**Figure S4.** EXAFS fittings of  $Ga1_{(500-air)}$  at Ga K-edge: magnitude (top) and imaginary (bottom) parts of the FT in R space.



**Figure S5.** EXAFS fittings of Ga1<sub>(650)</sub> at Ga K-edge: magnitude (top) and imaginary (bottom) parts of the FT in R space.



**Figure S6.** Wavelet transform (WT) analysis of EXAFS data for  $Ga1_{(500-air)}$  in the R range: (a) 0.5-4 Å and (b) 2-4 Å.



**Figure S7.** Wavelet transform (WT) analysis of EXAFS data for  $Ga1_{(650)}$  in the R range: (a) 0.5-4 Å and (b) 2-4 Å.



Figure S8. (a) ADF-STEM image and (b) EXD mapping of  $Ga1_{(650-air)}$ .





**Figure S9.** (a) Atomic and weight percentage of Ga content, (b) EDX spectrum and (c) ADF-STEM image and EDX mappings of a selected area of  $Ga1_{(650-air)}$ .



**Figure S10.** FTIR spectra of SOMC-prepared Ga@SiO<sub>2</sub> after evacuation at 650  $^{\circ}$ C and CO adsorption at a pressure of 20 Torr at room temperature.



Figure S11. FTIR spectra of SiO<sub>2</sub> in the hydroxyl region outgassed at 300, 400 or 550 °C.



Figure S12. FTIR comparison of the hydroxyl region of SiO<sub>2</sub> and Ga1<sub>(500-air)</sub> after evacuation at 300 °C.



**Figure S13.** Comparison of the <sup>71</sup>Ga MAS NMR spectra (obtained at 20.0 T with a spinning rate of 64 kHz) of Ga1<sub>(500-air)</sub> and Ga1<sub>(650-air)</sub> alongside the reference  $\beta$ -Ga<sub>2</sub>O<sub>3</sub>.



**Figure S14.** Propane conversion and product formation rate (mg  $h^{-1} g_{cat}^{-1}$ ) of C<sub>3</sub>H<sub>6</sub> (blue), C<sub>2</sub>H<sub>4</sub> (green) and CH<sub>4</sub> (yellow) on Ga1<sub>(650)</sub> over 20 h TOS.

Reaction conditions: 10% of  $C_3H_8$  in  $N_2$ , WHSV = 8.5 h<sup>-1</sup>, T = 550 °C.



**Figure S15.** Normalized propene formation rate ( $g_{C3H6}$  h<sup>-1</sup>  $g_{Ga}^{-1}$  m<sup>-2</sup>) on Ga1<sub>(650)</sub> over 25 h (5 × 5 h) TOS including four regeneration cycles (synthetic air, 550 °C, 1 h) performed after every 5 h.

Reaction conditions: 10% of C<sub>3</sub>H<sub>8</sub> in N<sub>2</sub>, WHSV = 8.5 h<sup>-1</sup>, T = 550 °C. We assumed that the regeneration cycles did not change the surface area of Ga1<sub>(650)</sub>.